

Docket No. 251475US3DIV

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Kousaku MATSUNO, et al.

SERIAL NO: New Application

GAU:

FILED: Herewith

EXAMINER:

FOR: SUBSTRATE TREATMENT PROCESS AND APPARATUS

INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97

COMMISSIONER FOR PATENTS
ALEXANDRIA, VIRGINIA 22313

SIR:

Applicant(s) wish to disclose the following information.

REFERENCES

- ☒ The applicant(s) wish to make of record the references listed on the attached form PTO-1449. Copies of the listed references were provided in parent application Serial No. 09/742,423 filed December 22, 2000, where required, as are either statements of relevancy or any readily available English translations of pertinent portions of any non-English language references.
- ☐ A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

RELATED CASES

- ☐ Attached is a list of applicant's pending application(s) or issued patent(s) which may be related to the present application. A copy of the patent(s), together with a copy of the claims and drawings of the pending application(s) is attached along with PTO 1449.
- ☐ A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

CERTIFICATION

- ☐ Each item of information contained in this information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- ☐ No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

DEPOSIT ACCOUNT

- ☒ Please charge any additional fees for the papers being filed herewith and for which no check or credit card payment is enclosed herewith, or credit any overpayment to deposit account number 15-0030. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

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MAIER & NEUSTADT, P.C.



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Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 251475US3DIV		SERIAL NO. New Application	
LIST OF REFERENCES CITED BY APPLICANT				APPLICANT Kousaku MATSUNO, et al.			
				FILING DATE Herewith		GROUP	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA	6,080,531	06/27/00	Carter et al.			
	AB	5,971,368	10/26/99	Nelson et al.			
	AC	5,983,909	11-1999	Yeol et al.			
	AD	6,920,777	09-2001	Imaoka et al.			
	AE	6,325,359	12-2001	Haga et al.			
	AF	5,503,708	04-1996	Koizumi et al.			
	AG	6,086,057	07-2000	Mitsumori et al.			
	AH	6,039,815	03-2000	Yeol et al.			
	AI	6,035,871	03-2000	Eui-Yeol, Oh			
	AJ	4,812,201	03-1989	Sakai et al.			
	AK	5,783,790	07-1998	Mitsumori et al.			
	AL	6,217,665	04-2001	Suzuki			
	AM	5,739,575	04-1998	Numano et al.			
	AN						
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO		
	AO	8-78372	03-1996	Japan (w/ abstract)		xx	
	AP	63-271938	11-1988	Japan (w/ abstract)		xx	
	AQ						
	AR						
	AS						
	AT						
	AU						
	AV						
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)							
	AW	S. Nelson: Using an ozone water last cleaning process to research the effects of process parameters on water contamination; SPWCC, pp. 230-242, March 4-7, 1996					
	AX	M. Hiroshi et al.: Dissolved-Gas Controlled Ultrapure Water Production System for Wet Cleaning Processes; The seventh International symposium on semiconductor manufacturing, proceedings of ISSM '98, Tokyo, pp. 428-431 (1998)					
	AY	M. Hiroshi et al.: Advanced UCT Cleaning Process Based on Specific Gases Dissolved Ultrapure Water; The eighth International symposium on semiconductor manufacturing, proceedings of ISSM '99 Tokyo, pp. 453-456 (1999)					
	AZ	M. Hiroshi et al.: Development of ozonated ultra-pure water supplying system using direct-dissolving method, SPWCC, pp. 51-60, March 13-16, 2000				<input checked="checked" type="checkbox"/> Additional References sheet(s) attached	
Examiner					Date Considered		
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

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				FILING DATE Herewith		GROUP	
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)							
	AAA	T. Ohmi et al.: Native oxide growth and organic impurity removal on Si surface with ozone injected ultrapure water, J. Electrochem. Soc., 140(3), 804-810, 1993					
	AAB	Werner Kern. Handbook of Semiconductor Cleaning Technology, 1993, Noyes Publications, Page 120.					
	AAC						
	AAD						
	AAE						
	AAF						
	AAG						
	AAH						
	AAI						
	AAJ						
	AAK						
	AAL						
	AAM						
	AAN						
	AAO						
	AAP						
	AAQ						
Examiner						Date Considered	
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